

FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

ATTORNEY DOCKET NO. 1945 P3 USA SILICON

SERIAL NO. N/A

LIST OF ART CITED BY APPLICANT

(Use several sheets if necessary.)

APPLICANT: Shen et al

FILING DATE: Herewith

GROUP: Unknown

U.S. PATENT DOCUMENTS

Examiner Initial		CLOCK NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>See</i>	A1	4	2	8	1	2	6	7	08/04/81	Kaveel	427	38	
<i>See</i>	A2	4	4	3		2	1	8	02/21/84	Nishimatsu et al	209	1055 R	
<i>See</i>	A3	4	4	6	5	5	1	2	08/14/84	Fukano	156	643	
<i>See</i>	A4	4	4	9	6	2	6	9	12/25/84	Hartman	156	643	
<i>See</i>	A5	4	5	0	2	9	1	4	03/07/85	Trumpp et al	156	643	
<i>See</i>	A6	4	5	7	6	6	8	2	05/18/86	Fukuta et al	204	165	
<i>See</i>	A7	4	7	0	5	5	8	3	11/10/87	Okudaira et al	156	643	
<i>See</i>	A8	4	7	3	8	7	4	4	04/19/88	Kira	156	643	
<i>See</i>	A9	4	7	8	6	3	1	2	11/21/88	Benzing	156	347	
<i>See</i>	A10	4	8	1	8	3	2	6	04/04/89	Imi et al	156	347	
<i>See</i>	A11	4	8	3	9	9	6	1	07/23/89	Sato et al	158	723	
<i>See</i>	A12	4	8	6	5	5	6	1	08/05/89	Freeman et al	156	646	
<i>See</i>	A13	4	8	6	7	8	4	1	09/19/89	Loewenstein et al	156	643	
<i>See</i>	A14	4	8	7	6	2	1	2	06/22/89	Koury	427	34	
<i>See</i>	A15	4	9	7	5	1	4	4	12/14/90	Yamazaki et al	156	643	
<i>See</i>	A17	4	9	9	4	4		6	02/19/91	Sun et al	427	192	
<i>See</i>	A18	5	0	1	1	6	1	2	02/26/91	Loewenstein et al	156	643	
<i>See</i>	A19	5	0	1	3	3	8	8	07/07/91	Long et al	156	643	
<i>See</i>	A20	5	0	3	7	7	6	8	07/30/91	Mi et al	156	626	
<i>See</i>	A21	5	0	8	4	1	2	6	07/28/92	McKee	156	343	
<i>See</i>	A22	5	0	9	4	7		2	06/16/92	Becker et al	156	643	
<i>See</i>	A23	5	1	1	6	4	6	8	05/08/92	Ijiri et al	156	643	
<i>See</i>	A24	5	1	1	6	4		6	05/08/92	Long	156	626	
<i>See</i>	A25	5	1	1	8	3	8	7	06/02/92	Kadomura	156	657	
<i>See</i>	A26	5	1	5	8	6	4	4	10/27/92	Cheung et al	156	643	
<i>See</i>	A27	5	1	6	0	4	0	7	11/03/92	Latchford et al	156	656	
<i>See</i>	A28	5	1	6	4	3	1	0	11/17/92	Davis et al	427	192	
<i>See</i>	A29	5	1	7	6	7	9	2	01/05/93	Lullowan et al	156	652	
<i>See</i>	A30	5	1	8	8	9	8	0	02/23/93	Lai	427	193	

10510 U.S. PTO
09/507629
02/18/00

EXAMINER: Initial of reference considered, whether or not citations in conformance with MPEP 1706. If not in conformance and not considered, attach copy of this form with next communication to applicant.

FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

ATTORNEY DOCKET NO. 1945 P3 USA SILICON

SERIAL NO. N/A

LIST OF ART CITED BY APPLICANT

(Use several sheets if necessary.)

APPLICANT: Shen, et al

FILING DATE: Herewith

GROUP: Unknown

U.S. PATENT DOCUMENTS

Examiner Initial		DOCKET NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>He</i>	A31	1		9	2	7	0	9	05/06/94	Useng	437	47	
<i>He</i>	A32		2	0	7	8	3	6	05/06/94	Chang	134	1	
<i>He</i>	A33		2	8	6	2	4	5	10/26/94	Keller, et al	156	643	
<i>He</i>	A34		2	8	1	5	0	7	05/25/94	Gabric, et al	156	643	
<i>He</i>	A35		2	8	2	8	9	9	02/01/94	Balnashonov, et al	158	723 R	
<i>He</i>	A36				2	5	1	9	06/17/94	Sakai, et al	154	1	
<i>He</i>	A37				8	6	6	8	06/07/94	Lunaki, et al	156	662	
<i>He</i>	A38				8		9	8	03/26/94	Szwedkowski, et al	156	655	
<i>He</i>	A39			3	4	4	1	7	10/11/94	Cheung, et al	156	643	
<i>He</i>	A40			3	6	4	7	8	10/18/94	Chen, et al	154	1	
<i>He</i>	A41			3	8	6	0	3	10/25/94	Cathey	156	656	
<i>He</i>	A42			3	7	8	5	1	07/03/95	Nagayama, et al	156	64	
<i>He</i>	A43			3	2		1	6	06/17/95	Hills, et al	156	643	
<i>He</i>	A44			3	9	1	9	7	07/14/95	Ishimaru	156	643	
<i>He</i>	A45				3		5	4	06/09/95	Aydil, et al	157	81	
<i>He</i>	A46			4		1	7	7	07/11/95	Rabin, et al	656	633	
<i>He</i>	A47			4	3	6	8	6	05/22/95	Jones, et al	256	37	
<i>He</i>	A48			4	9	4	7		05/12/95	Fukuda, et al	158	723 MP	
<i>He</i>	A49			5	4	6	2	2	05/07/96	Bornstein, et al	437	189	
<i>He</i>	A50			5	2	1	1	0	05/28/96	Chen, et al	437	187	
<i>He</i>	A51			5	9	1	0	7	06/25/96	Orewal	256	68	
<i>He</i>	A52			6	2	0	6	3	04/15/97	Keller	438	720	
<i>He</i>	A53			6	2	6	7	7	07/06/97	Roberts, et al	256	67	
<i>He</i>	A54			6		7	1	7	06/01/97	Ogordim, et al	256	67	
<i>He</i>	A55			6	4	4	5	5	07/01/97	Keller	257	324	
<i>He</i>	A56			7	3	5	5	3	05/19/98	Saito	437	192	
<i>He</i>	A57			7	6	4	0	6	05/26/98	Ye, et al	438	710	
<i>He</i>	A58			7	6	7	0	2	06/16/98	Imai, et al	438	710	
<i>He</i>	A59			7	8	8	7	8	08/11/98	Shang, et al	154	1	
<i>He</i>	A60			7	8	8	9	9	08/04/98	Steger, et al	156	343	

EXAMINER

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FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

ATTORNEY DOCKET NO. 1945 P3 USA SILICON

SERIAL NO. N/A

LIST OF ART CITED BY APPLICANT

(Use several sheets if necessary)

APPLICANT: Shen, et al

FILING DATE: Herewith

GROUP: Unknown

U.S. PATENT DOCUMENTS

EXAMINER Initial	DOCKET NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (if appropriate)
<i>Shen</i>	A61	8 1 1 0 2 2	09/02/98	Savas, et al	216 68	
<i>Shen</i>	A62	8 1 7 5 3 4	10/06/98	Ye, et al	438 30	
<i>Shen</i>	A63	8 4 3 2 3 9	12/01/98	Shrotriva	134 11	
<i>Shen</i>	A64	8 4 9 0 9 2	12/15/98	Xi, et al	134 11	
<i>Shen</i>	A65	8 6 6 4 8 3	02/02/99	Shiau, et al	438 720	
<i>Shen</i>	A66	8 6 9 4 0 1	02/09/99	Brunemeier, et al	438 710	
<i>Shen</i>	A67	8 7 4 3 6 3	02/23/99	Hon, et al	438 721	
<i>Shen</i>	A68	8 7 9 5 7 5	03/09/99	Iepman, et al	216 68	
	A69					
	A70					
	A71					
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	A88					
	A89					
	A90					

EXAMINER Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Attach copy of this form with next communication to applicant.

FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

ATTORNEY DOCKET NO. 1945 P3 USA SILICON

SERIAL NO. N/A

LIST OF ART CITED BY APPLICANT

(Use several sheets if necessary)

APPLICANT: Shen et al

FILING DATE: 11/11/01

GROUP: Packaging

FOREIGN PATENT DOCUMENTS

		DOCKET NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
													YES	NO
<i>Shen</i>	B1	0	2	7	2	1	4	3	06.22.88	EP Application				
<i>Shen</i>	B2	0	3	1	4	9	9	0	05.10.89	EP Application				
<i>Shen</i>	B3	0	4	6	3	3	7	3	01.02.92	EP Application				
<i>Shen</i>	B4	0	5	1	6	0	4	3	12.02.92	EP Application				
<i>Shen</i>	B5	0	5	5	5	5	4	6	08.18.93	EP Application				
<i>Shen</i>	B6	0	6	9	7	4	6	7	02.21.96	EP Application				
<i>Shen</i>	B7	0	7	4	6	0	1	5	12.04.96	EP Application				
<i>Shen</i>	B8	0	7	9	0	6	3	5	02.05.97	EP Application				
<i>Shen</i>	B9	4	1	3	2	5	5	9	04.08.93	German Application			✓	
<i>Shen</i>	B10	6	1	7	7	0	9	2	06.24.94	Japan			✓	
<i>Shen</i>	B11	7	0	2	9	8	7	9	01.31.95	Japan			✓	
<i>Shen</i>	B12	9	6	1	5	5	4	5	05.23.96	PCI				
<i>Shen</i>	B13													
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EXAMINER

Alkan Chen

DATE CONSIDERED

2/6/02

EXAMINER'S NOTE: This communication is being made by the examiner in accordance with the provisions of 37 CFR 1.104(b) and 1.104(c). This communication is not intended to constitute an offer of patent protection, nor is it intended to constitute a promise of patent protection. It is intended to provide information to the applicant regarding the status of the application and to provide an opportunity for the applicant to comment on the information provided.

FORM P10-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTORNEY DOCKET NO. 1945 P3 USA SILICON		SERIAL NO. N/A	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary.)				APPLICANT: Shen, et al			
				FILING DATE: 11/1/91		GROUP: P. 1. 000000	
OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)							
	C1	Aydi, et al. "Multiple Steady States in a Radio Frequency Chlorine Glow Discharge" <u>J. Appl. Phys.</u> , Volume 69, No. 1, January 1, 1991, pages 109-114					
	C2	Hillemeier, S.J., et al. "A Symmetric Submicron CMOS Technology" <u>IEEE</u> , pages 232-237, 1987					
	C3	PCI Notification of International Search Report dated October 28, 1990					
	C4	PCI Notification of International Search Report dated February 4, 1990					
	C5						
	C6						
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	C8						
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						DATE CONSIDERED	
EXAMINER: Initial if reference considered, whether or not citation is in conformance with art. 13.1 of the Rules. Attach a copy of this form with next communication to applicant.							

PENDING U.S. PATENT APPLICATIONS

ATTORNEY DOCKET NO.: 1945.P3/USA/SILICON
 SERIAL NUMBER: N/A
 FILING DATE: HEREWITH
 INVENTORS: SHEEN, ET AL

EXAMINER INITIAL		PENDING U.S. PATENT APPLICATIONS
<i>Acw</i>	D1	U.S. Patent Application entitled, "Method for Improved Cleaning of Substrate Processing System"; filed July 11, 1997; Serial No. 08/893,922; Inventors: Kao, et al.
	D2	U.S. Patent Application entitled, "Apparatus for Improved Remote Microwave Plasma source for Use with Substrate Processing Systems"; filed April 23, 1997; Serial No. 08/839,111; Inventors: Kao, et al.
	D3	U.S. Patent Application entitled, "Method and Apparatus for Determining the Endpoint in a Plasma Cleaning Process"; filed July 2, 1997; Serial No. 08/887,165; Inventors: Subrahmanyam, et al.
	D4	U.S. Patent Application entitled, "Apparatus and Method for Efficient and Compact Remote Microwave Plasma Generation"; filed April 22, 1997; Serial No. 08/839,007; Inventor: Bhatnagar
	D5	U.S. Patent Application entitled, "Method and Apparatus for Pre-stabilized Plasma Generation for Microwave Clean Applications"; filed November 13, 1996; Serial No. 08/746,658; Inventors: Fong, et al.
	D6	U.S. Patent Application entitled, "Inductively Coupled HDP-CVD Reactor"; filed May 29, 1997; Serial No. 08/877,018; Inventors: Redeker, et al.
	D7	U.S. Patent Application entitled, "Symmetric Tunable Inductively Coupled HDP-CVD Reactor"; filed July 15, 1996; Serial No. 08/679,927; Inventors: Redeker, et al.
	D8	U.S. Patent Application entitled, "Apparatus and Methods for Upgraded Substrate Processing System with Microwave Plasma Source"; filed March 5, 1997; Serial No. 08/811,627; Inventors: Tanaka, et al.
<i>Acw</i>	D9	U.S. Patent Application entitled, "Microwave Apparatus for In-situ Vacuum Line Cleaning for Substrate Processing Equipment"; filed October 30, 1996; Serial No. 08/741,241; Inventors: Pang, et al.
	D10	
	D11	
	D12	
	D13	
	D14	

FORM PTO-1149

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

ATTORNEY DOCKET NO. 1945 P/SILICON CHANGAS

SERIAL NO. 09 867 629

LIST OF ART CITED BY APPLICANT
(Use several sheets if necessary)

APPLICANT: SHEN J. L. M.

GROUP: 1746

FILED DATE: 2/18/00

U.S. PATENT DOCUMENTS

Examiner initials		DOCKET NUMBER								DATE	NAME	CLASS	SUBCLASS	CITING DIV. I II APPROPRIATE
		1	2	3	4	5	6	7	8					
<i>hlc</i>	AA	1	-	3	8	-	4	8		1/1/88	GEN.	75	647	
<i>hlc</i>	AB	1	-	-	9	9	9	1		1/1/89	DOCKERY	48	719	
	AC													
	AD													
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	AH													
	AI													
	AJ													
	AK													

FOREIGN PATENT DOCUMENTS

		DOCKET NUMBER								DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
		1	2	3	4	5	6	7	8					YES	NO
	AL														
	AM														
	AN														
	AO														
	AP														

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

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DATE CONSIDERED: 2/2/00

EXAMINER: (initial) Reference considered whenever it is pertinent
to the communication to applicant

FORM PTO-149

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

ATTORNEY DOCKET NO. 1945 P3 USA SILICON

SERIAL NO.
09 507 629

LIST OF ART CITED BY APPLICANT

(Use several sheets if necessary)

APPLICANT: Shen, et al

FILING DATE: 02/18/2000

GROUP: Unknown 1774

U.S. PATENT DOCUMENTS

Examiner Initial		DOCKET NUMBER							DATE	NAME	CLASS	SUBCLASS	TRANSLATION IF APPROPRIATE
<i>for</i>	AA	5	7	0	0	7	4	1	12/23/97	Liao	425	723 123	
<i>for</i>	AB	6	0	0	0	7	1	8	07/18/00	Hanme, et al	425	714	
	AC												RECEIVED
	AD												
	AE												
	AF												700
	AG												
	AH												
	AI												

FOREIGN PATENT DOCUMENTS

		DOCKET NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
													YES	NO
<i>for</i>	AI	0	1	0	5	0	4	27	02/27/89	Japan			(X) Abstract only	
<i>for</i>	AK	1	0	2	3	3	8	7	09/02/98	Japan				X
<i>for</i>	AL	0	7	0	0	8	7	2	05/01/96	JP			X	
	AM													
	AN													

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

<i>for</i>	AO	PCT Search Report dated 11/8/00
	AP	
	AQ	

EXAMINER

DATE CONSIDERED 2/1/00

EXAMINER Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant



FORM PTO 610

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

ATTORNEY DOCKET NO. 02045 USA PCT EICH SILICON JB

SERIAL NO.
099,847,629

LIST OF ART CITED BY APPLICANT

(For design patents, unnecessary)

APPLICANT: Shen, et al

FILING DATE: 02/18/02

CLASSIFICATION

U.S. PATENT DOCUMENTS

Examiner Initial		DOCKET NUMBER								DATE	NAME	CLASS	SUBCLASS	FILING DATE (If Appropriate)
<i>Hee</i>	AA	5		4	1	3	9	6		4/2/98	Loewenstein	162	642.1	
<i>Hee</i>	AB	5	6	5	7	8	8	6		07/29/97	Keller et al	162	642.1	
	AC													
	AD													
	AE													
	AF													
	AG													
	AH													
	AI													

FOREIGN PATENT DOCUMENTS

		DOCKET NUMBER								DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
														YES	NO
<i>Hee</i>	AI	5	8	3	7	4	9	7		4/22/98	EP				
<i>Hee</i>	AK						8	7		4/22/98	EP				
	AL														
	AM														
	AN														

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

<i>Hee</i>	AO	PCT Report dated 06/22/01, European Patent Office, P.B. 5818 Patentlaan 2 NL-2280 HV Rijswijk												
<i>Hee</i>	AP	Zaleski, et al " Tungsten Silicide Polysilicon Stack Etching using Mixed Fluorine Chlorine Chemistry in a High Density Plasma Chamber", Electrochemical Society Proceedings Volume 98-4, pages 203-209												
<i>Hee</i>	AQ													

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

JAN 17 2002

FORM PTO 449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		DOCKET NO. 007451 USA POSTECH SILEICON IR		APPLICATION NO. 62,867,679							
INFORMATION DISCLOSURE STATEMENT IN AN APPLICATION				APPLICANT: Sher et al.		JURISDICTION UNKNOWN							
U.S. PATENT DOCUMENTS													
EXAMINER INITIAL	DOCUMENT NUMBER								DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
Jus Jus Jus	1	2	3	4	5	6	7	8	06/28/95	Wang et al.	722	618.2	
	9	10	11	12	13	14	15	16	06/28/95	H. et al.	156	613	
	17	18	19	20	21	22	23	24	06/28/95	Okada et al.	156	613	
<div style="border: 1px solid black; padding: 5px; transform: rotate(-10deg); display: inline-block;"> RECEIVED FEB - 4 2002 TC 1700 </div>													
FOREIGN PATENT DOCUMENTS													
DOCUMENT NUMBER								DATE	NAME	CLASS	SUBCLASS	TRANSLATION	
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)													
EXAMINER: <i>Jus Jus Jus</i>												DATE CONSIDERED: 3/2/02	
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.													